

AMENDMENTS TO THE SPECIFICATION

Please delete the present Abstract of the Disclosure.

Please add the following new Abstract of the Disclosure:

A method of forming a metal oxide film by the plasma CVD method and which
includes~~comprising~~ reacting chiefly an organometal by a glow discharge in a low output region
and, then, reacting the organometal with an oxidizing gas by the glow discharge in a high-output
region to form a metal oxide film on the surface of a plastic substrate via an organic layer. This
method forms a thin film having excellent adhesiveness, softness and flexibility on the surface of
a plastic substrate relying on the plasma CVD method.